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(71)Applicant : JSR CORP
NIPPON TOKUSHU COATING KK

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(72)Inventor : TAKAHASHI TOSHIHIKO
TAKASE HIDEAKI
TAKEHATA YUICHI
UKAJI TAKASHI

(54) RADIATION-CURABLE RESIN COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a photoresetting resin composition that is excellent in adhesion to and fast-curability with a resin, a reflection membrane and a semipermeable membrane constituting optical disks and in resistances to heat and moisture in the hardened products and simultaneously shows a high light transmission to a beam for reading out recorded informations, and is useful as an adhesive for optical disks.

SOLUTION: This photoresetting resin composition contains (A) urethane (meth) acrylate, (B) a phosphoric ester bearing at least one (meth)acryloyl group in one molecule, (C) a (meth)acrylate bearing at least one (meth)acryloyl group in one molecule other than the components A and B, (D) a compound bearing a mercapto group and a specific organosilyl group in one molecule and (E) a photopolymerization initiator.

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